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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

MUNAKA

Serial No.: New Application

Group Art Unit:

Filed: September 18, 2001

Examiner:

For: WAFER STORAGE CASE, PROCESS FOR PREVENTING DUST GENERATION
THEREOF AND WAFER STORING METHOD

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

September 18, 2001

Sir:

Prior to calculation of the filing fee and prior to the examination of this application, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend claims as follows.

8. (Amended) The process for preventing dust generation of a wafer storage case according to any of claims 3 to 6, wherein the wafer storage case to be coated with the coating agent is a cleaned wafer storage case.

10. (Amended) The process for preventing dust generation of a wafer storage case according to any of claims 3 to 6, wherein the coating agent is a surfactant.

12. (Amended) A wafer storing method comprising the steps of:
preparing wafers; and
housing the wafers in a wafer storage case treated by a process for
preventing dust generation of a wafer storage case according to any of claims 3 to 6.

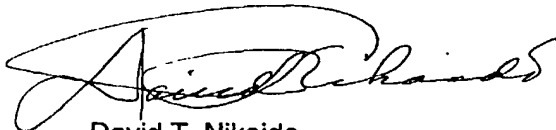
REMARKS

The above amendments to the claims have been made to correct the multiple dependency of the claims and to put the application in better condition for examination. No new matter has been added.

In the event that any fees are due in connection with this paper, please charge our Deposit Account No. 01-2300.

Respectfully submitted,

ARENT FOX KINTNER PLOTKIN & KAHN, PLLC



David T. Nikaido
Attorney for Applicant
Reg. No. 22,663

Atty. Docket No.: P107242-00021

Arent Fox Kintner Plotkin & Kahn, PLLC
1050 Connecticut Avenue, N.W., Suite 600
Washington, D.C. 20036-5339
Telephone No. (202) 857-6000
Facsimile No. (202) 638-4810

DTN/hk

CLAIMS

1. A wafer storage case of synthetic resin housing wafers, wherein a surface of the wafer storage case is coated with a coating layer of a coating agent to prevent dust generation from the surface.
2. The wafer storage case according to claim 1, wherein the coating agent is a surfactant.
3. A process for preventing dust generation of a wafer storage case comprising the steps of:
- 10 coating a surface of the wafer storage case of synthetic resin housing wafers with a coating agent;
- drying the wafer storage case coated with the coating agent;
- cleaning the dried wafer storage case using pure water such that a coating layer of the coating agent remains across the surface of the wafer storage case; and
- 15 drying the cleaned wafer storage case,
- wherein dust generation from the surface of the wafer storage case is prevented by the coating layer of the coating agent.
4. A process for preventing dust generation of a wafer storage case comprising a step of:
- 20 coating a surface of the wafer storage case of synthetic resin housing wafers with a coating agent;
- cleaning the wafer storage case using pure water such that a coating layer of the coating agent remains across the surface of the wafer storage case; and
- 25

drying the cleaned wafer storage case,

wherein dust generation from the surface of the wafer storage case is prevented by the coating layer of the coating agent.

5. The process for preventing dust generation of a wafer storage case according to claim 4, wherein the pure water used in the step of cleaning with the pure water such that the coating layer of the coating agent remains across the surface of the wafer storage case is pure water with a low specific resistance.

6. The process for preventing dust generation of a wafer storage case according to claim 5, wherein the pure water with a low specific resistance has a specific resistance of 10 MΩ·cm or less.

7. The process for preventing dust generation of a wafer storage case according to any of claims 3 to 6, wherein by immersing the wafer storage case in an aqueous solution of a coating agent, the surface of the wafer storage case is coated with the coating agent.

8. The process for preventing dust generation of a wafer storage case according to any of claims 3 to ~~6~~, wherein the wafer storage case to be coated with the coating agent is a cleaned wafer storage case.

9. The process for preventing dust generation of a wafer storage case according to claim 8, wherein the cleaned wafer storage case is a wafer storage case cleaned with surfactant cleaning and pure water cleaning.

10. The process for preventing dust generation of a wafer storage case according to any of claims 3 to ~~6~~, wherein the coating agent is a surfactant.

11. A wafer storing method comprising the steps of:
preparing wafers; and

housing the wafers in a wafer storage case according to claim 1 or 2.

12. A wafer storing method comprising the steps of:

preparing wafers; and

housing the wafers in a wafer storage case treated by a process for

5 preventing dust generation of a wafer storage case according to any of claims

3 to ~~10~~. 6